



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Barnes, et al.

Serial No.: 09/931,324

Confirmation No.: 3945

Filed: August 16, 2001

For: Adjustable Dual
Frequency Voltage
Dividing Plasma Reactor

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Group Art Unit: 1765

Examiner: Binh X. Tran

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on March 5, 2003 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.	
Date March 5, 2003	Signature <i>[Signature]</i>

RESPONSE TO OFFICE ACTION DATED DECEMBER 5, 2002

In response to the Office Action dated December 5, 2002, having a shortened statutory period for response set to expire on March 5, 2003, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicants believe that no fee is due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4184/ETCH/CHMBR/JB1, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE CLAIMS:

Please cancel claims 25-33 without prejudice and amend the claims as follows:

1. (Amended) An apparatus for processing a substrate, comprising:
a chamber having a first electrode disposed therein;